

Figure 1

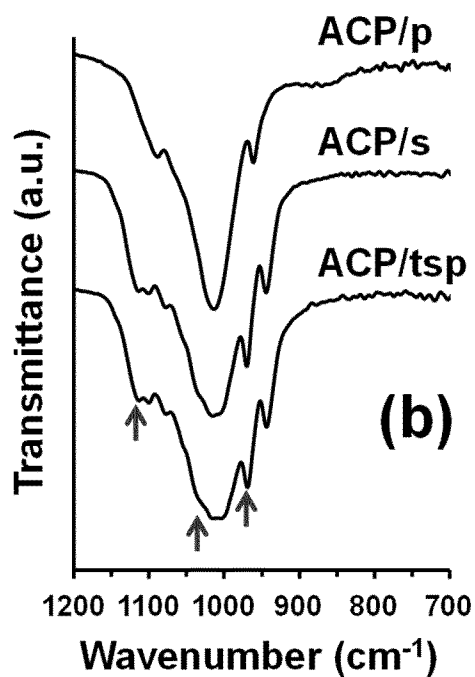
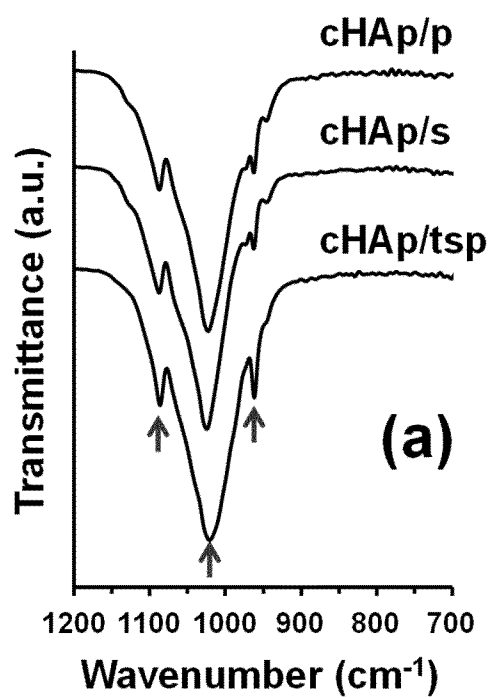
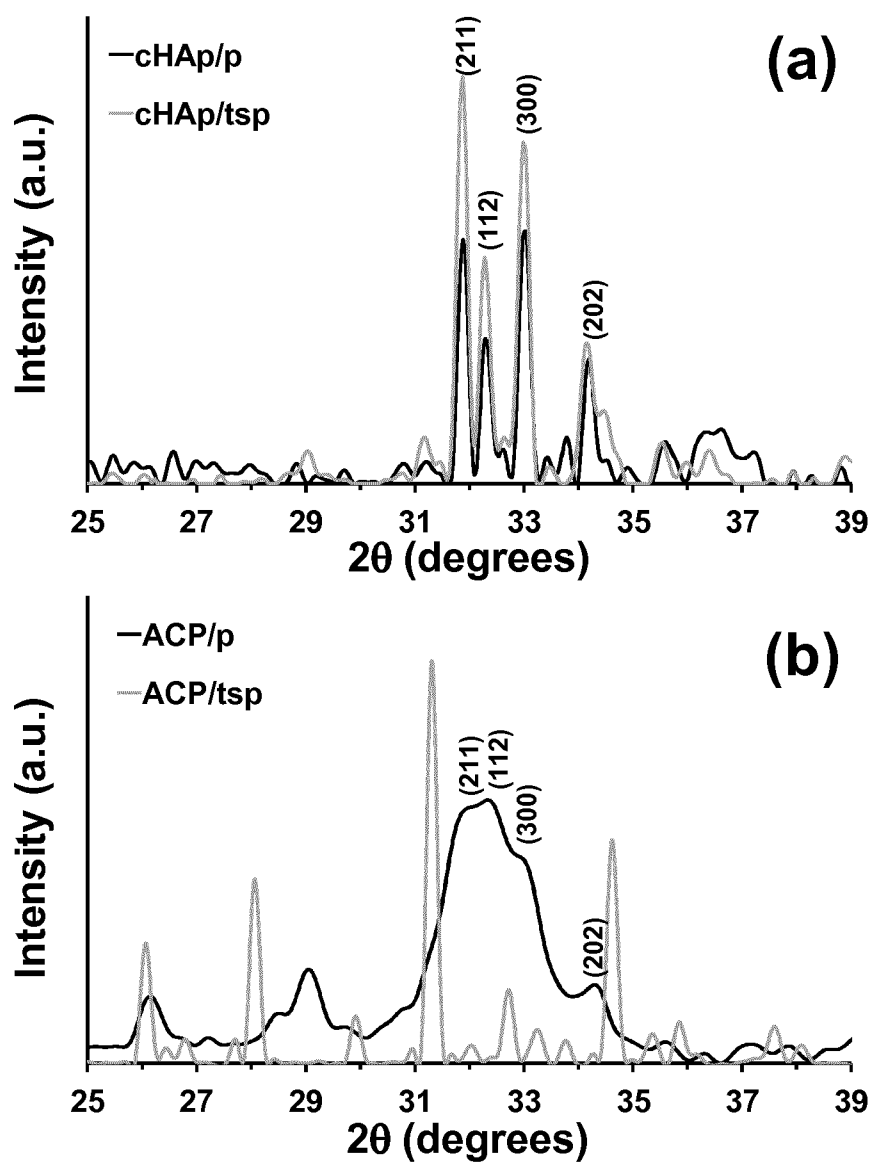


Figure 2



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Figure 3

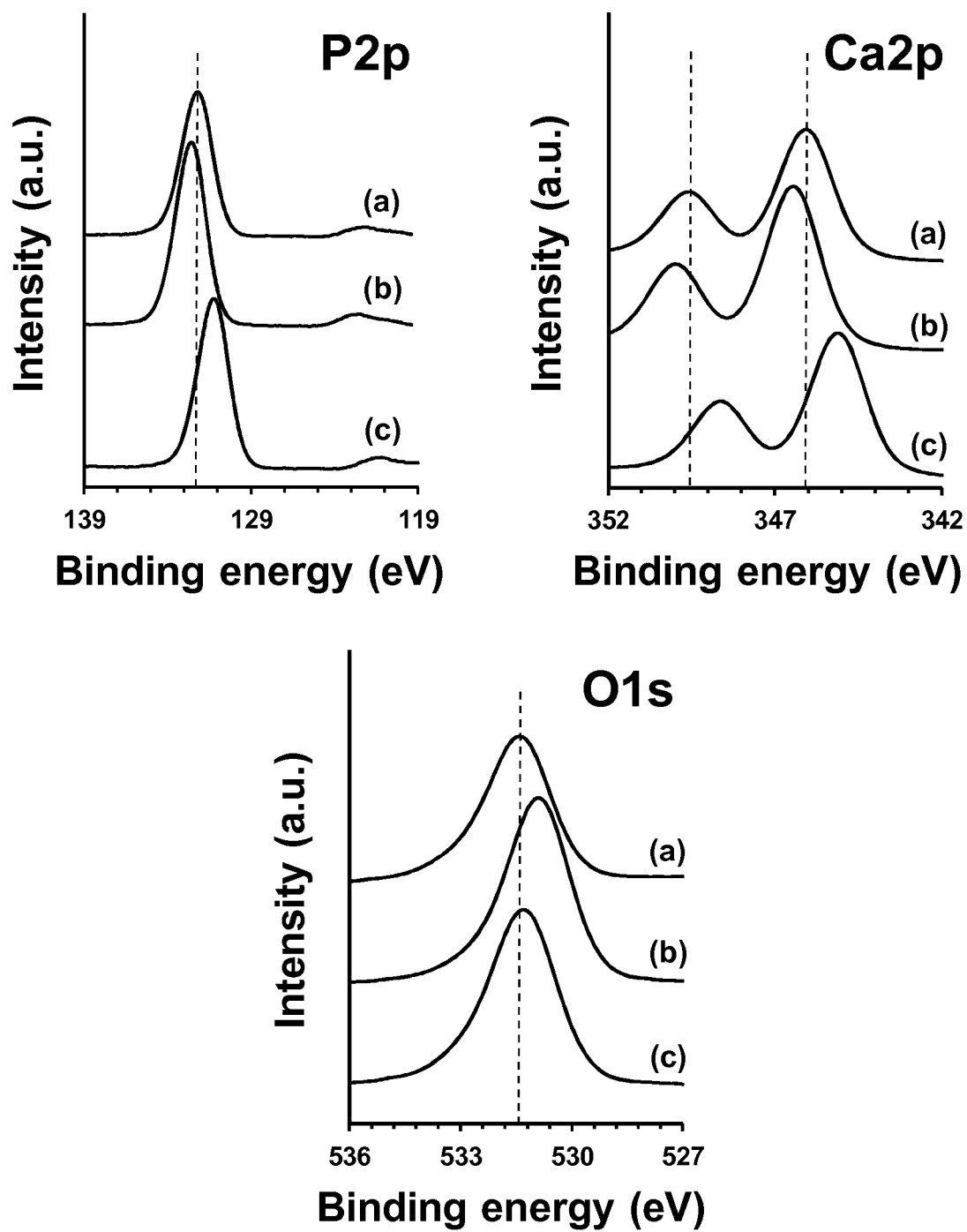
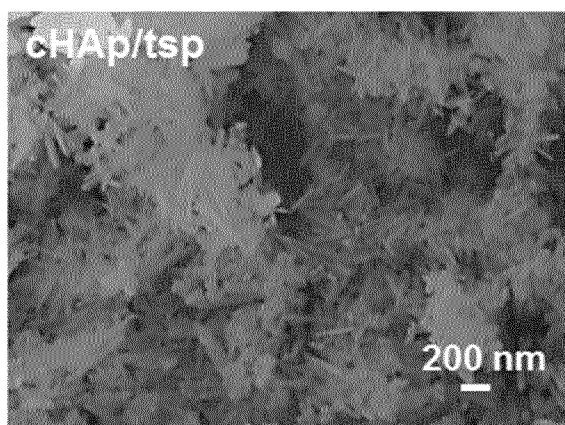
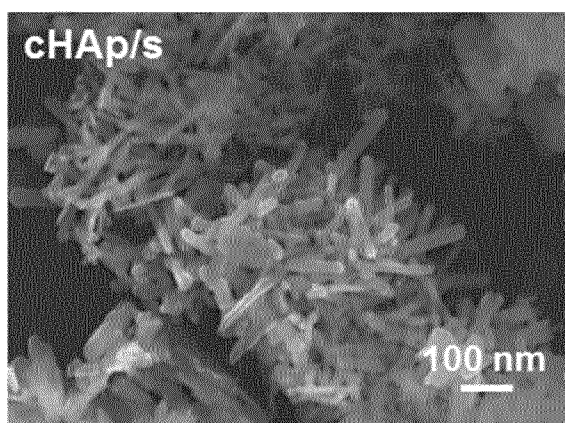
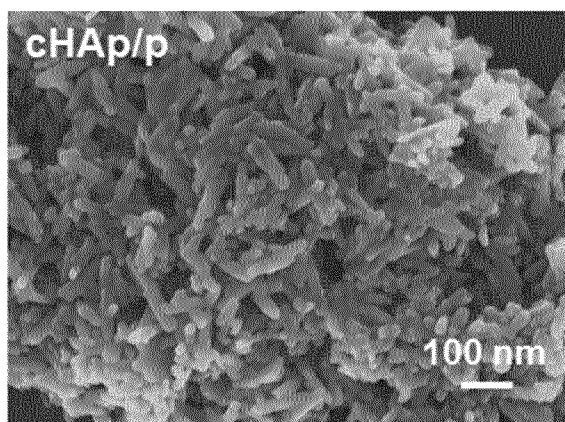


Figure 4



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Figure 5

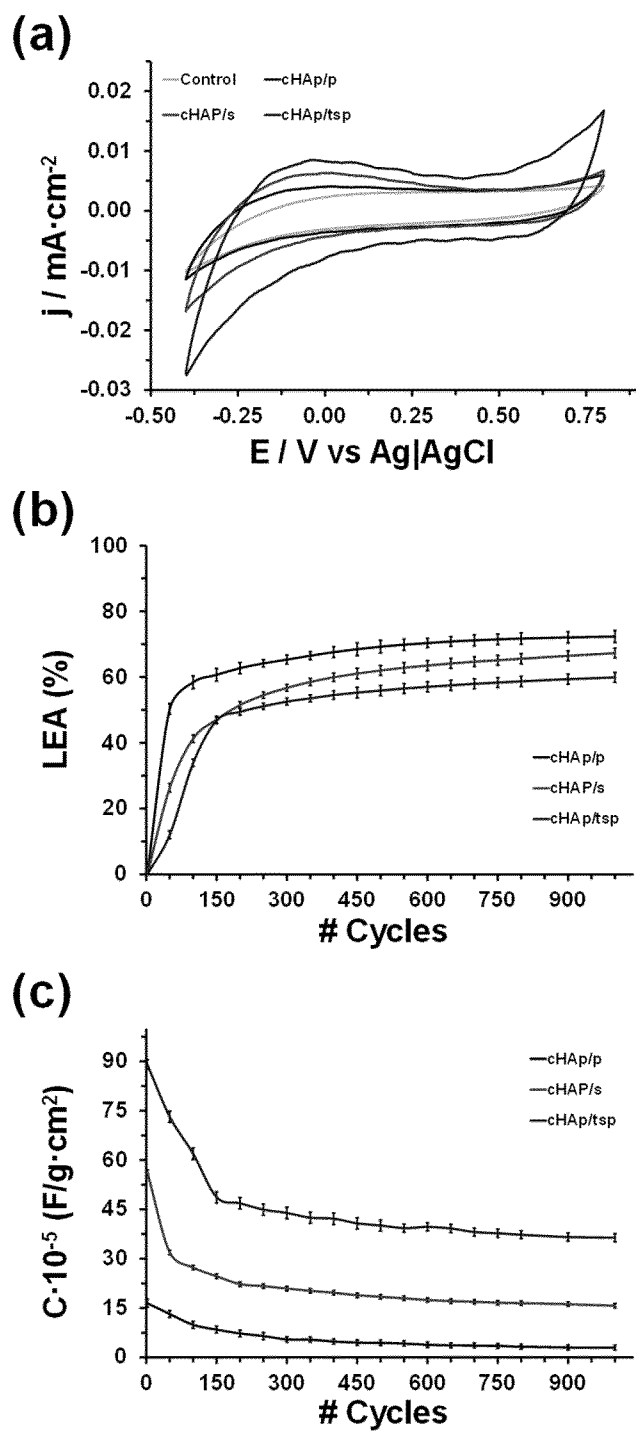
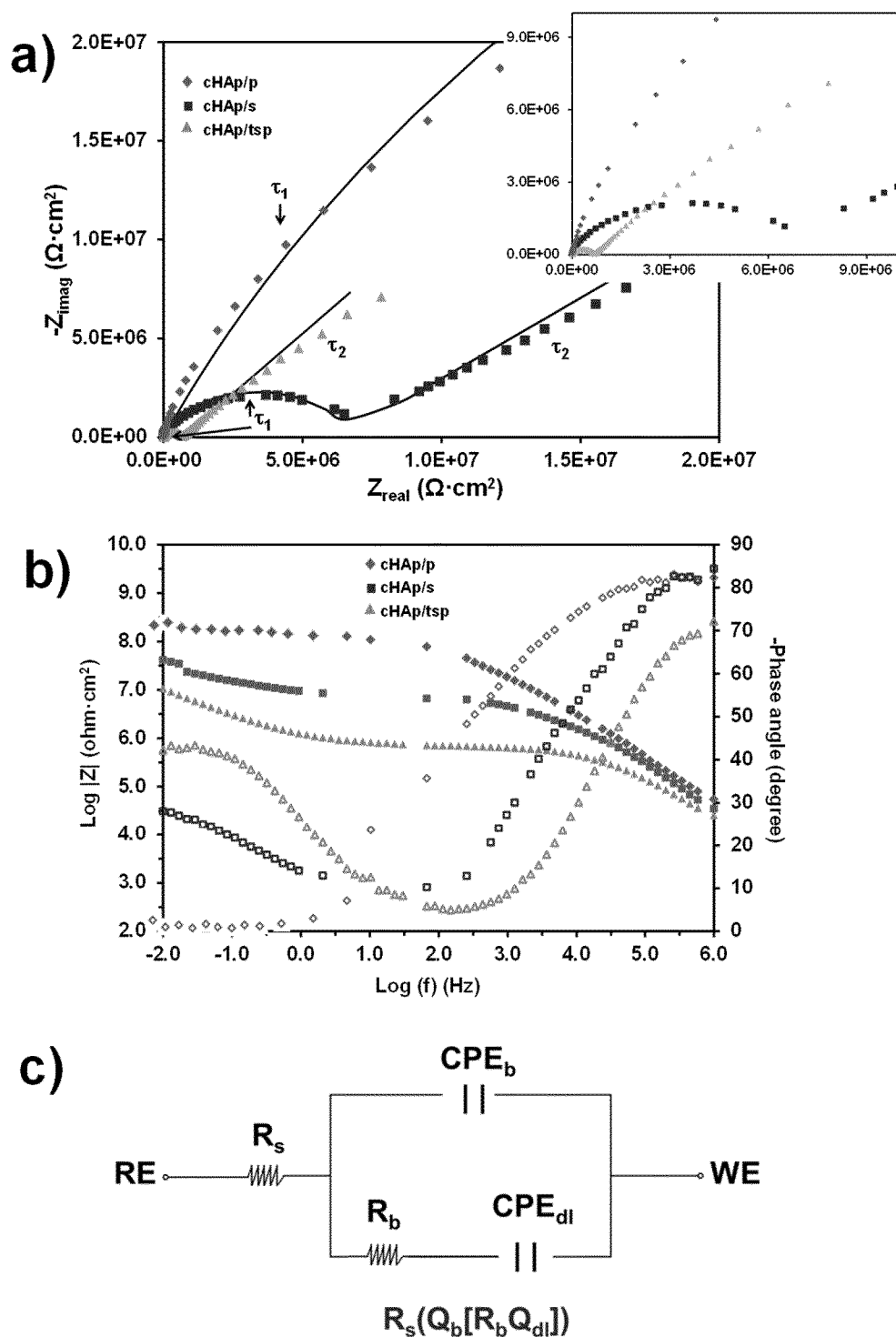


Figure 6



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Figure 7

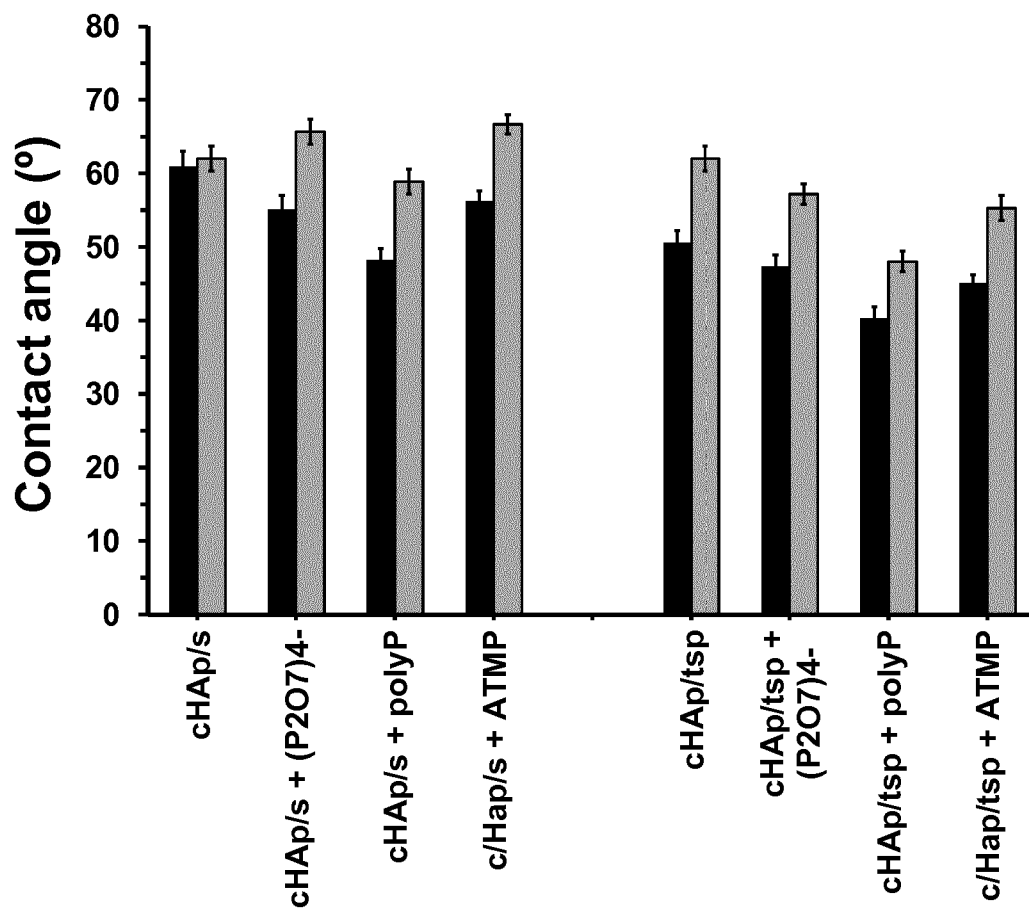


Figure 8

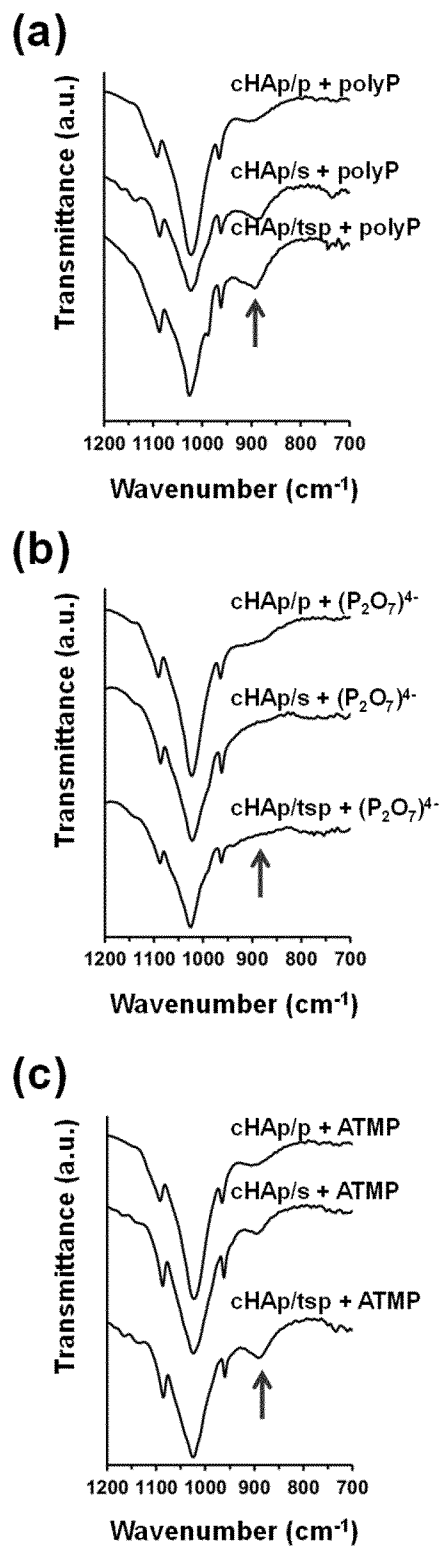
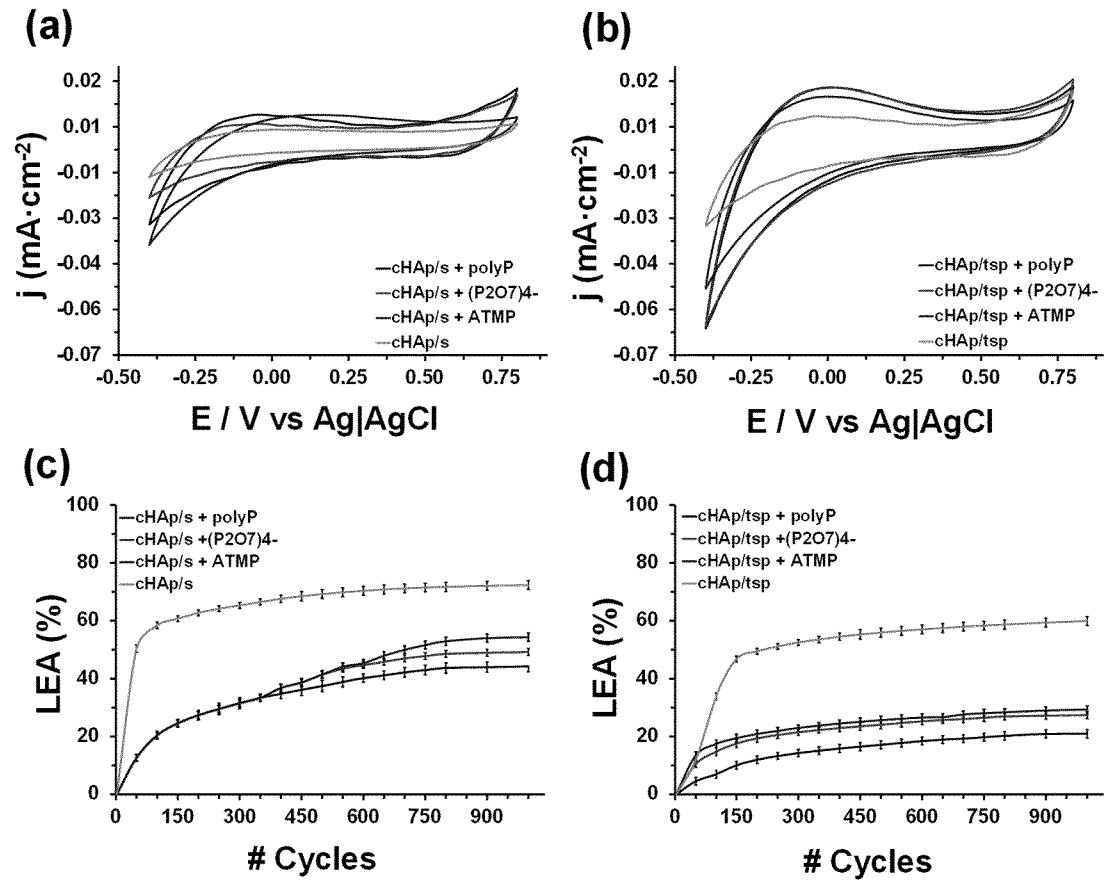
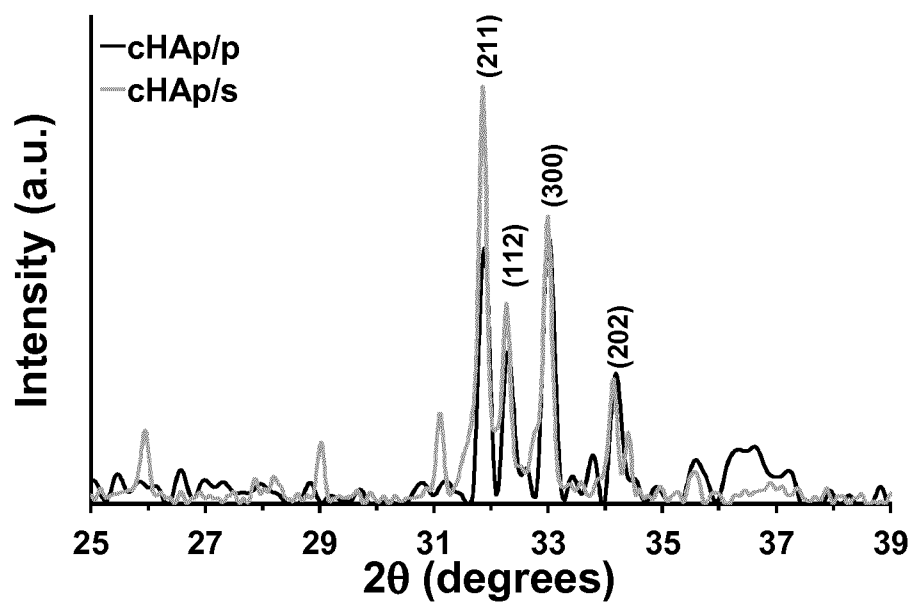


Figure 9



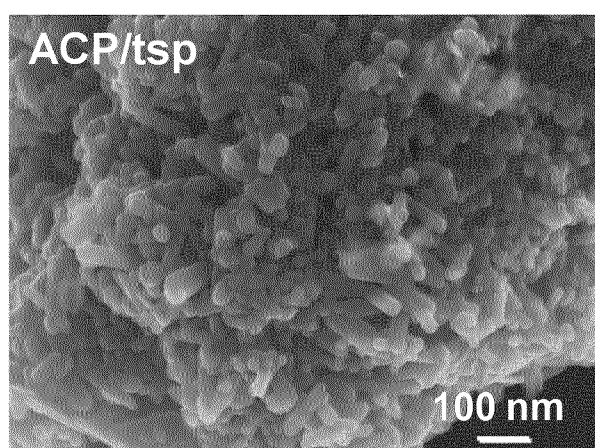
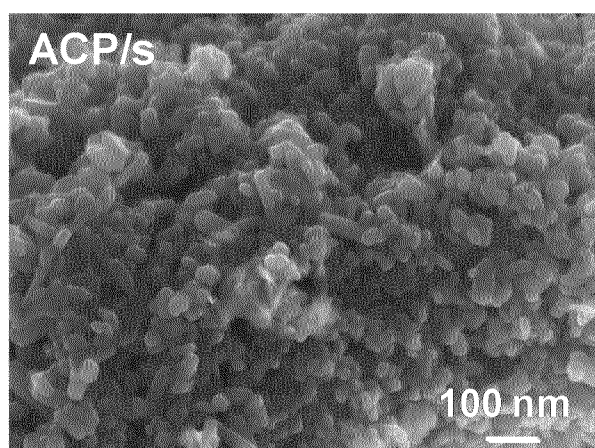
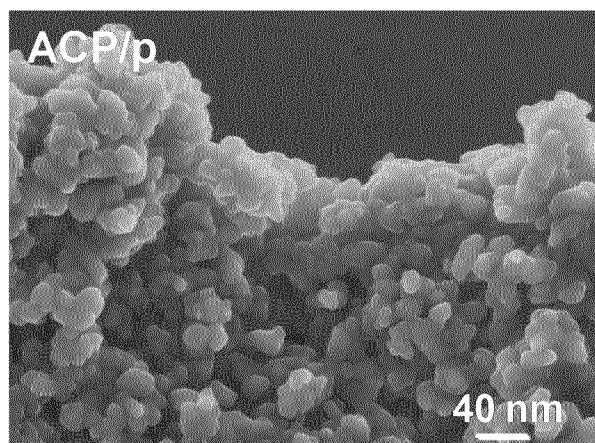
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Figure 10



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Figure 11



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Figure 12

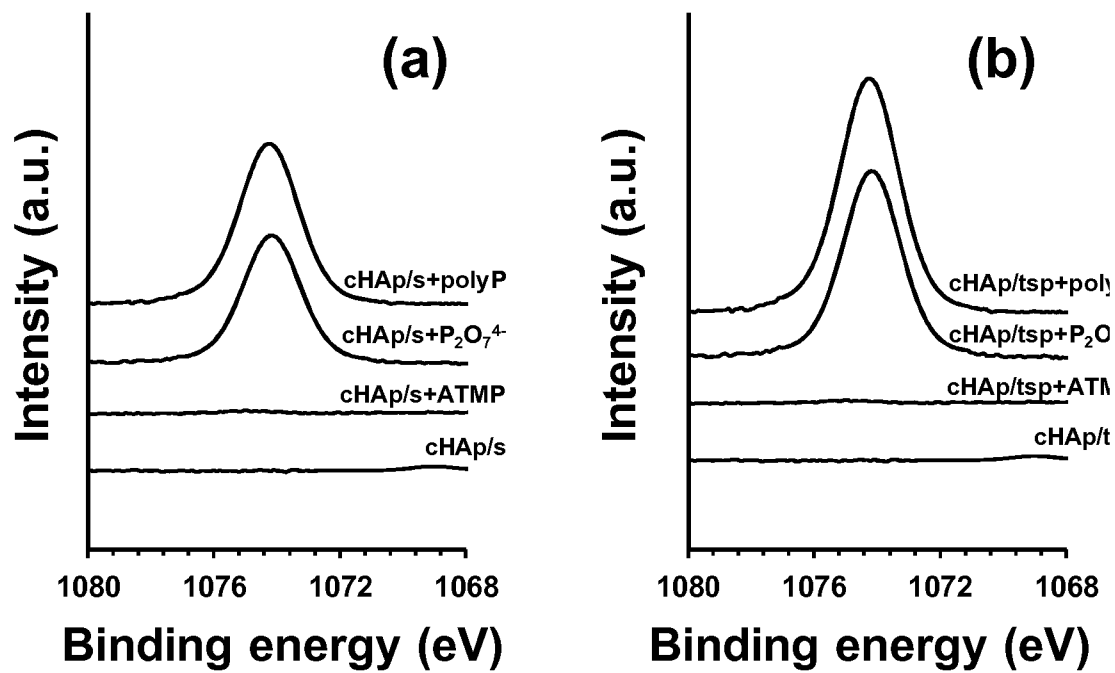


Figure 13

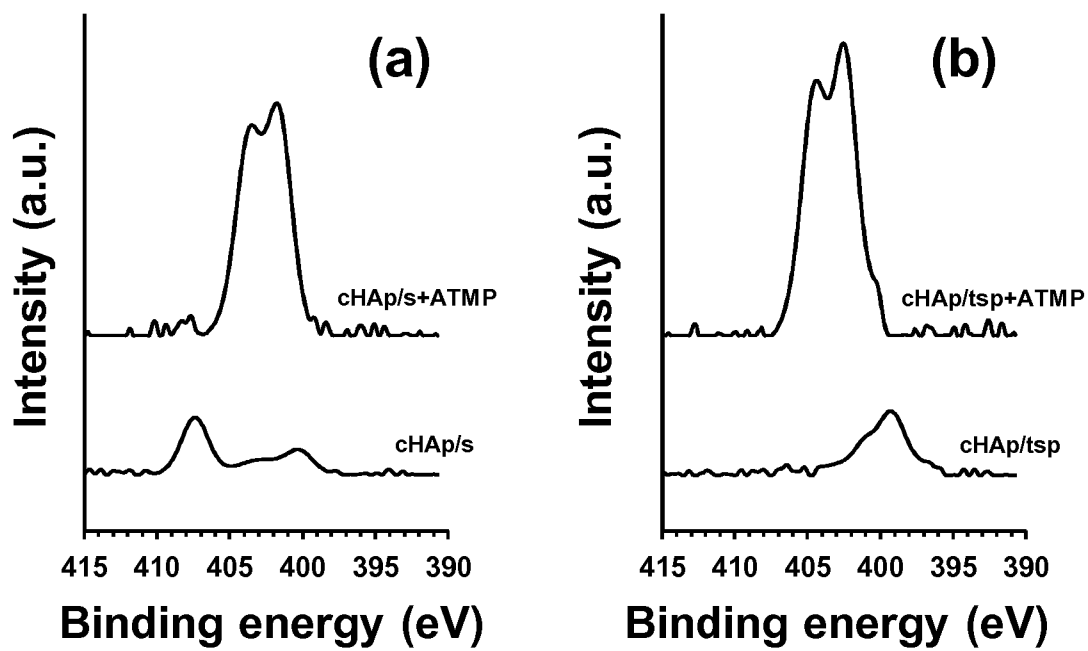


Figure 14

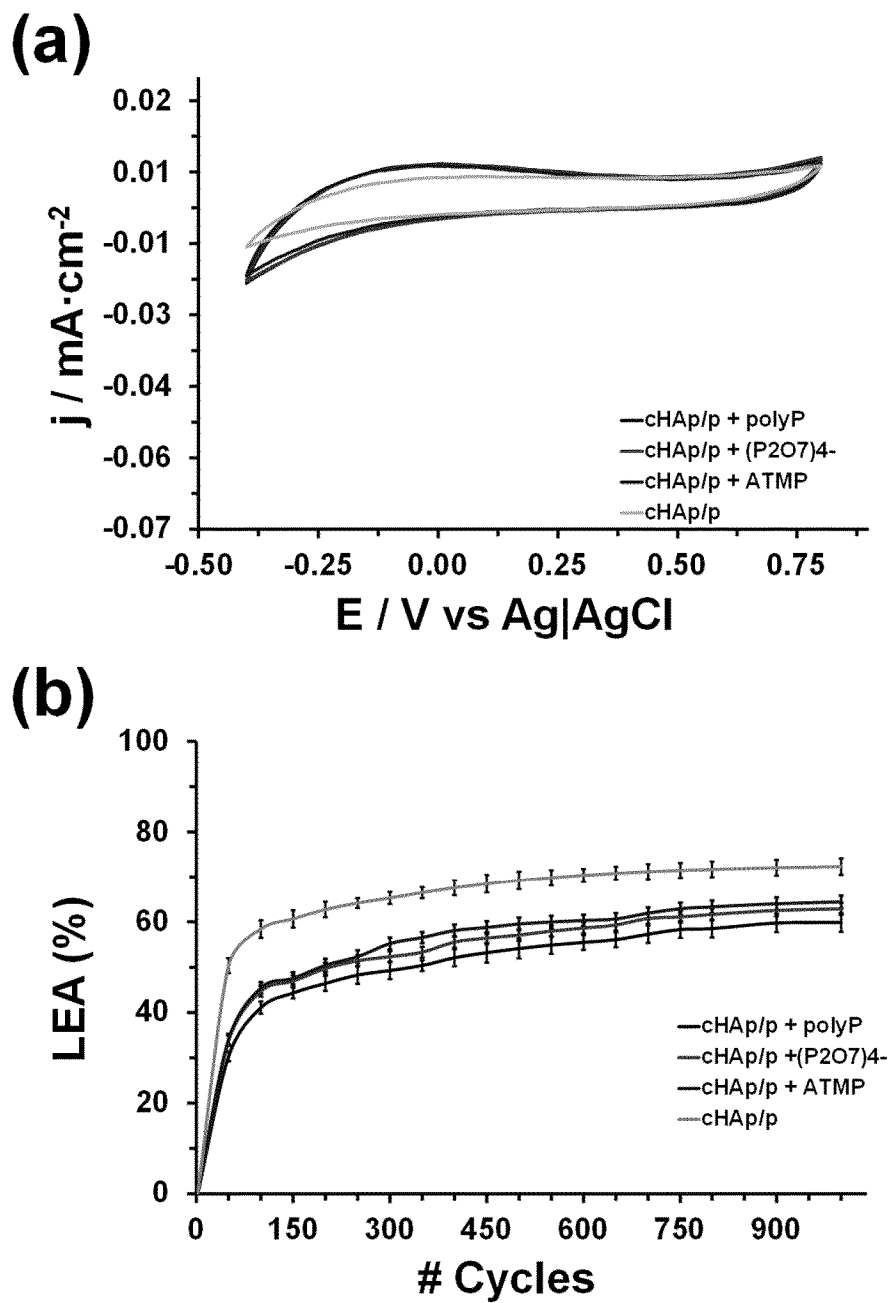


Figure 15

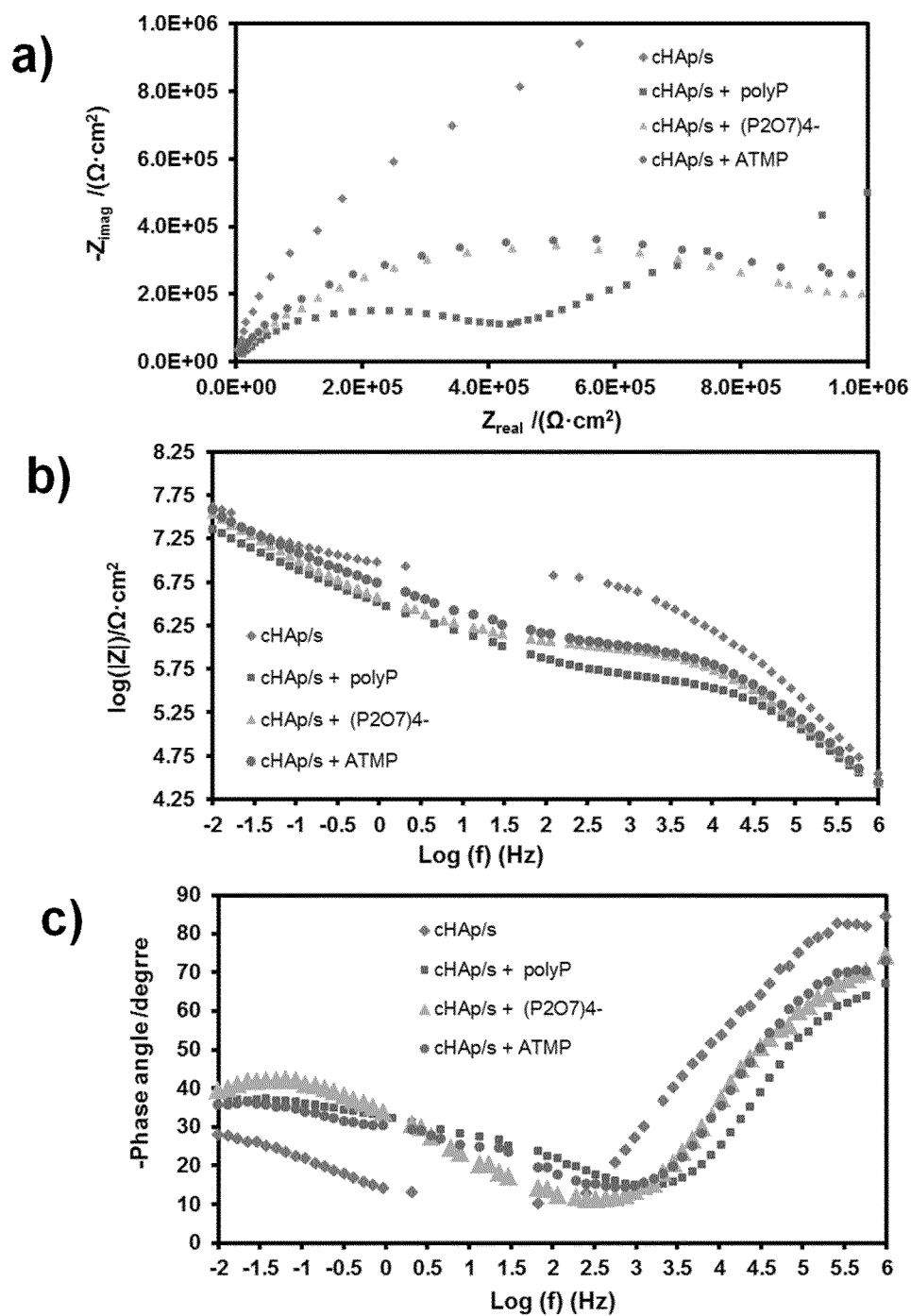
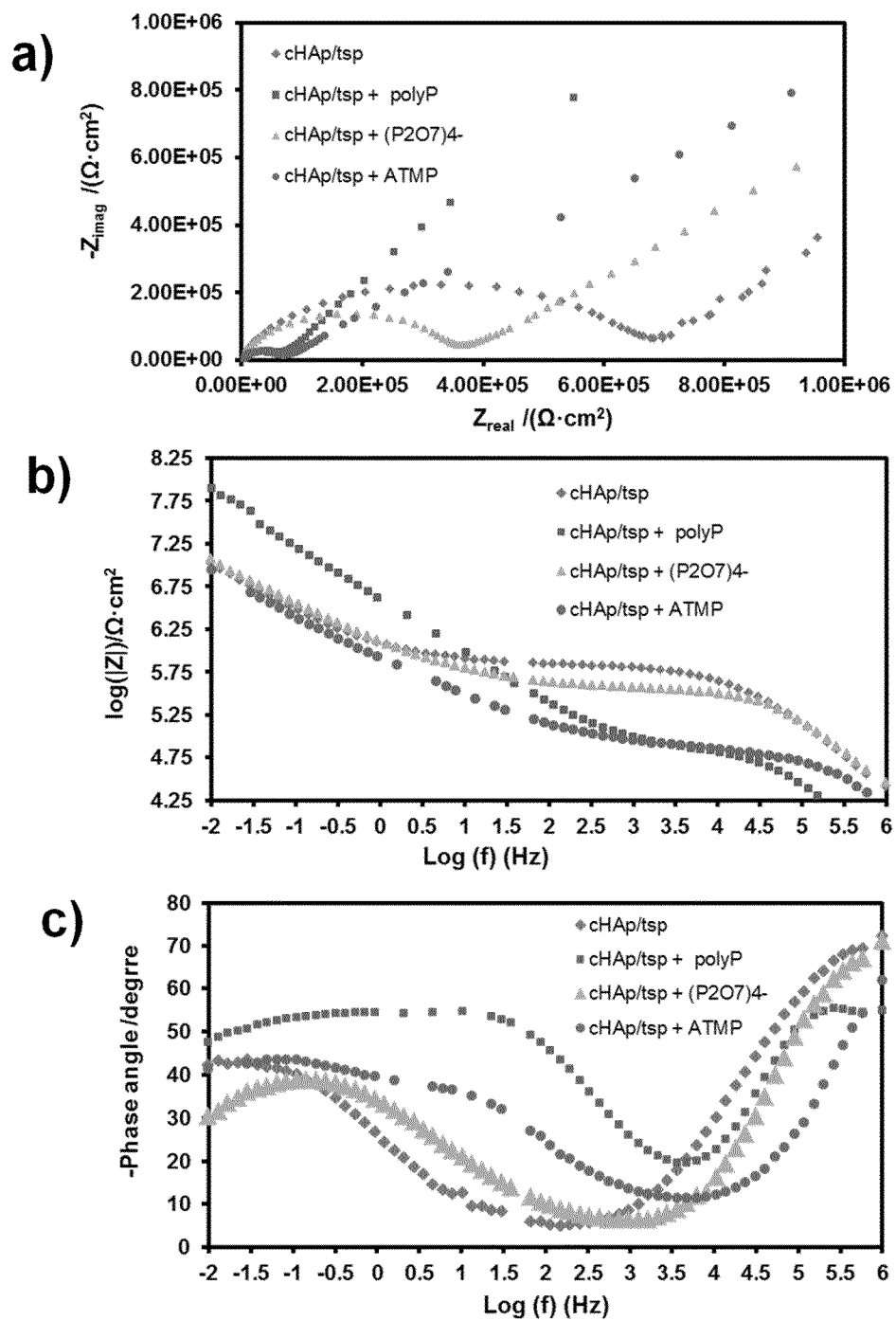
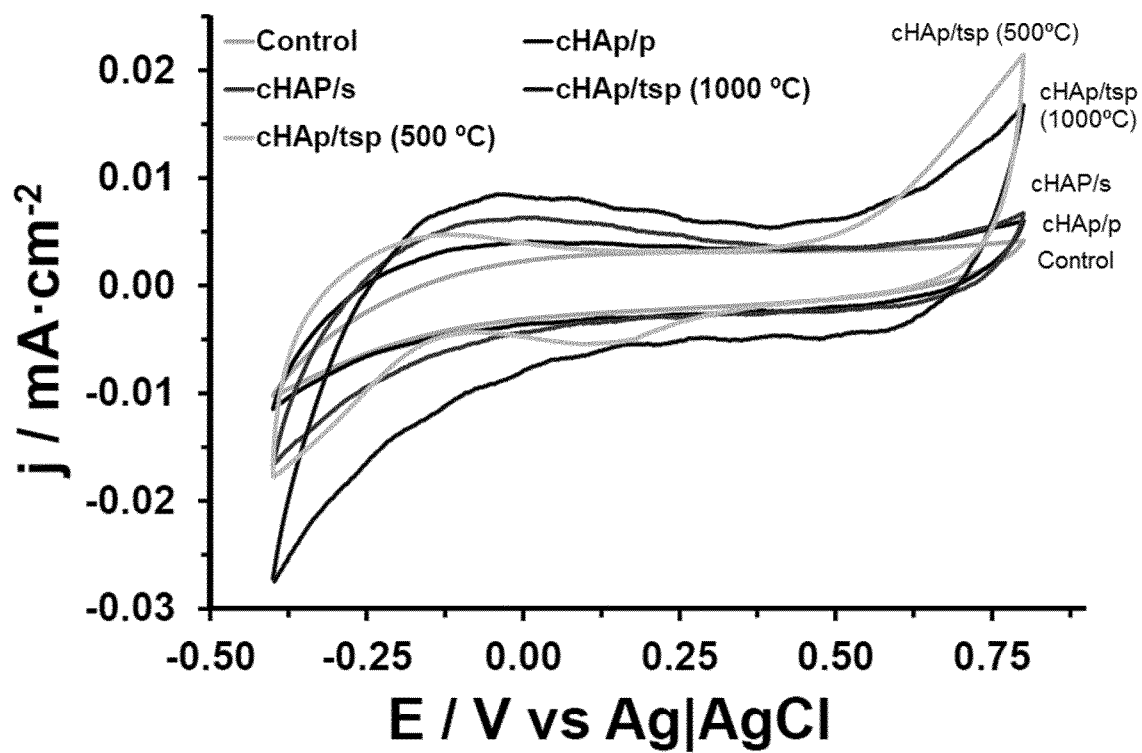


Figure 16



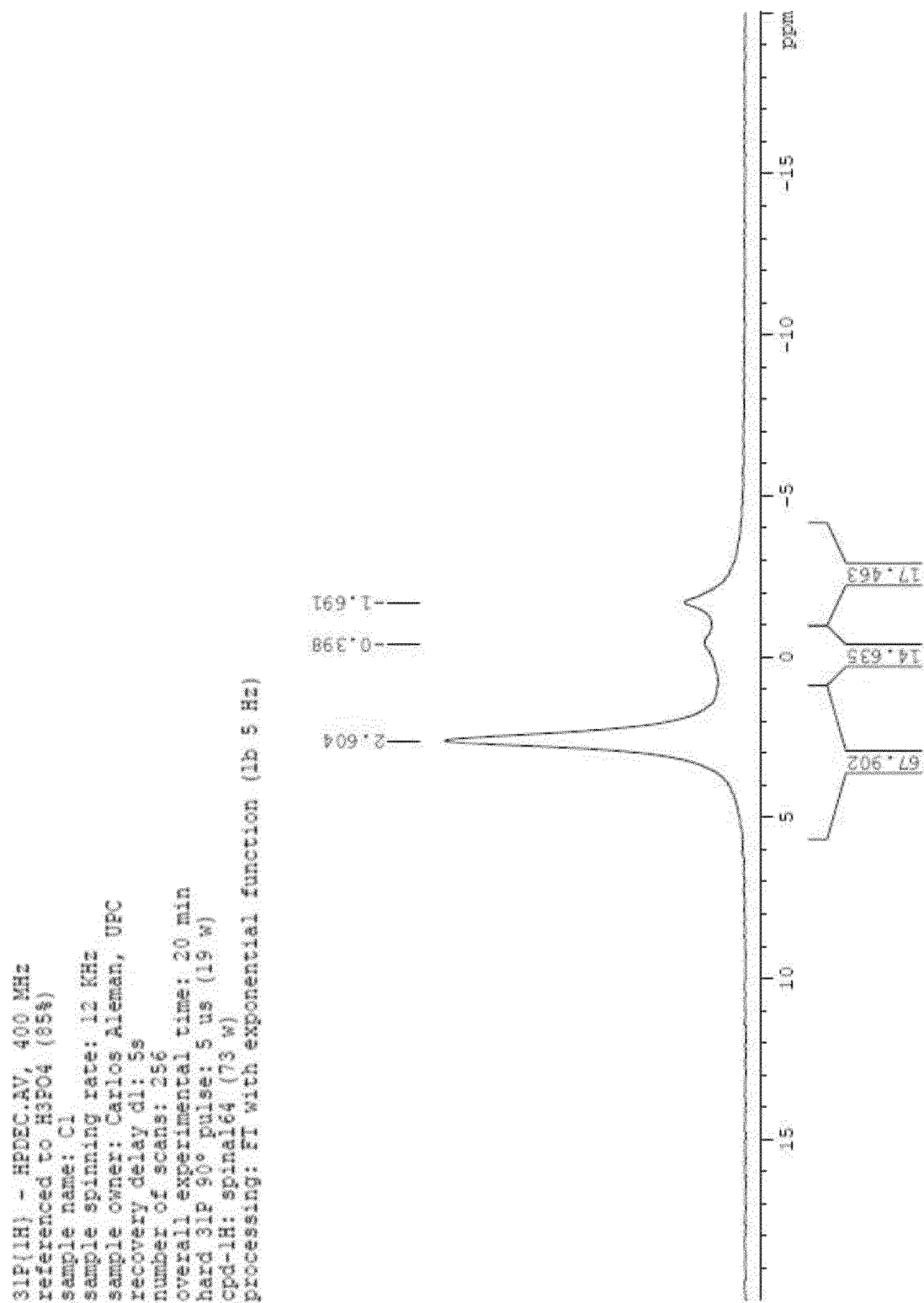
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Figure 17



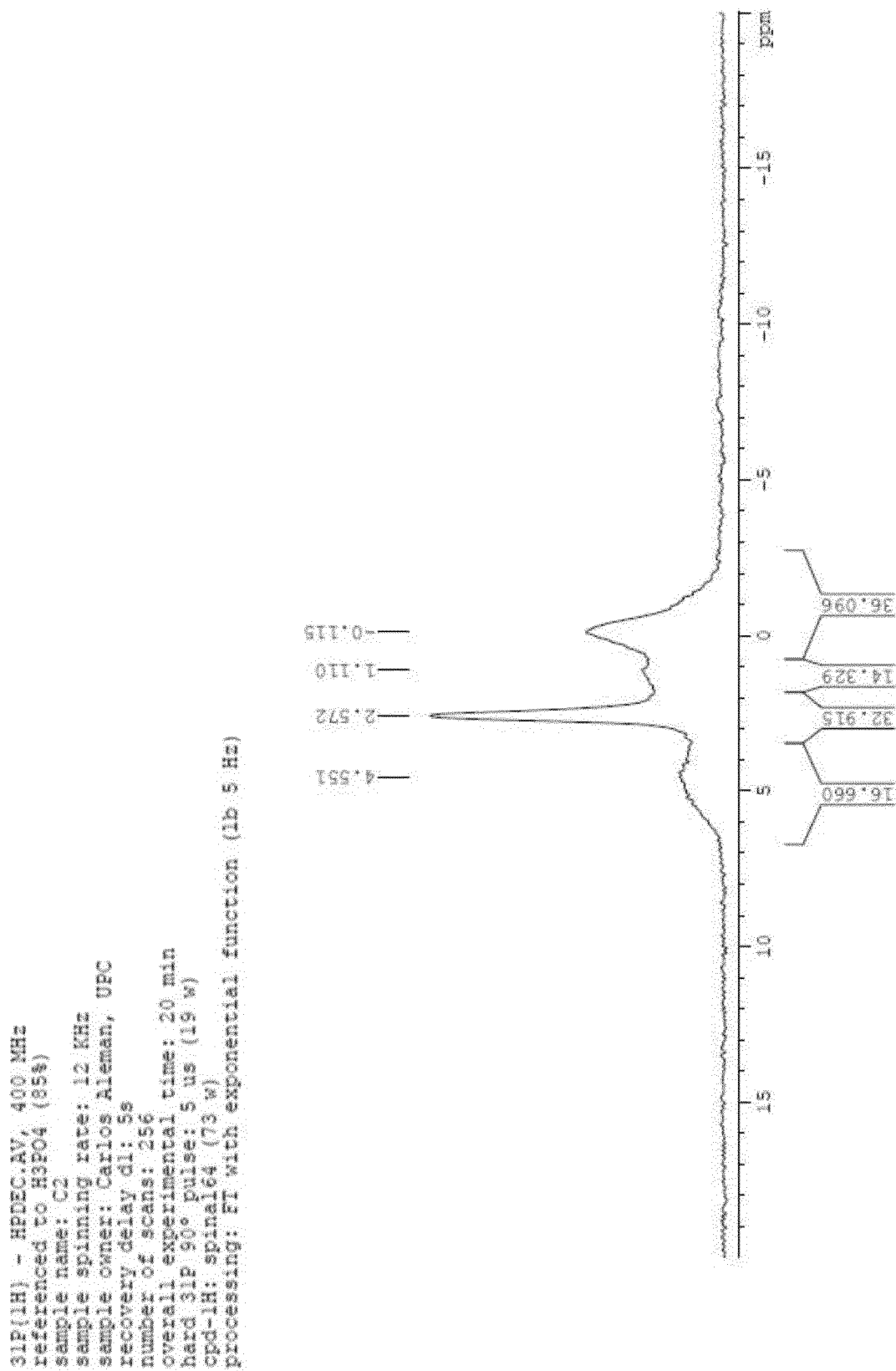
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Figure 18A



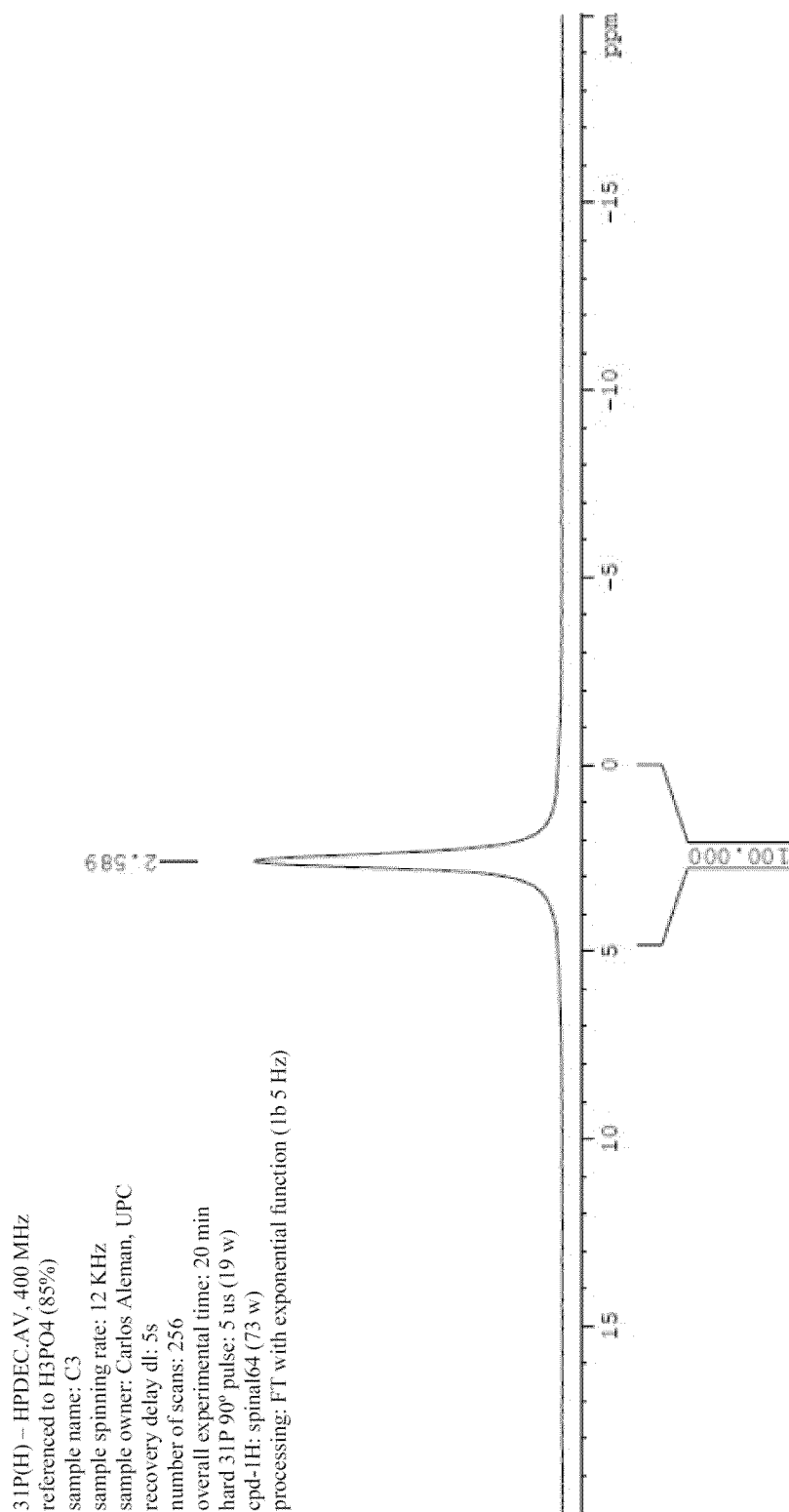
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Figure 18B



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Figure 18C



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Figure 18D

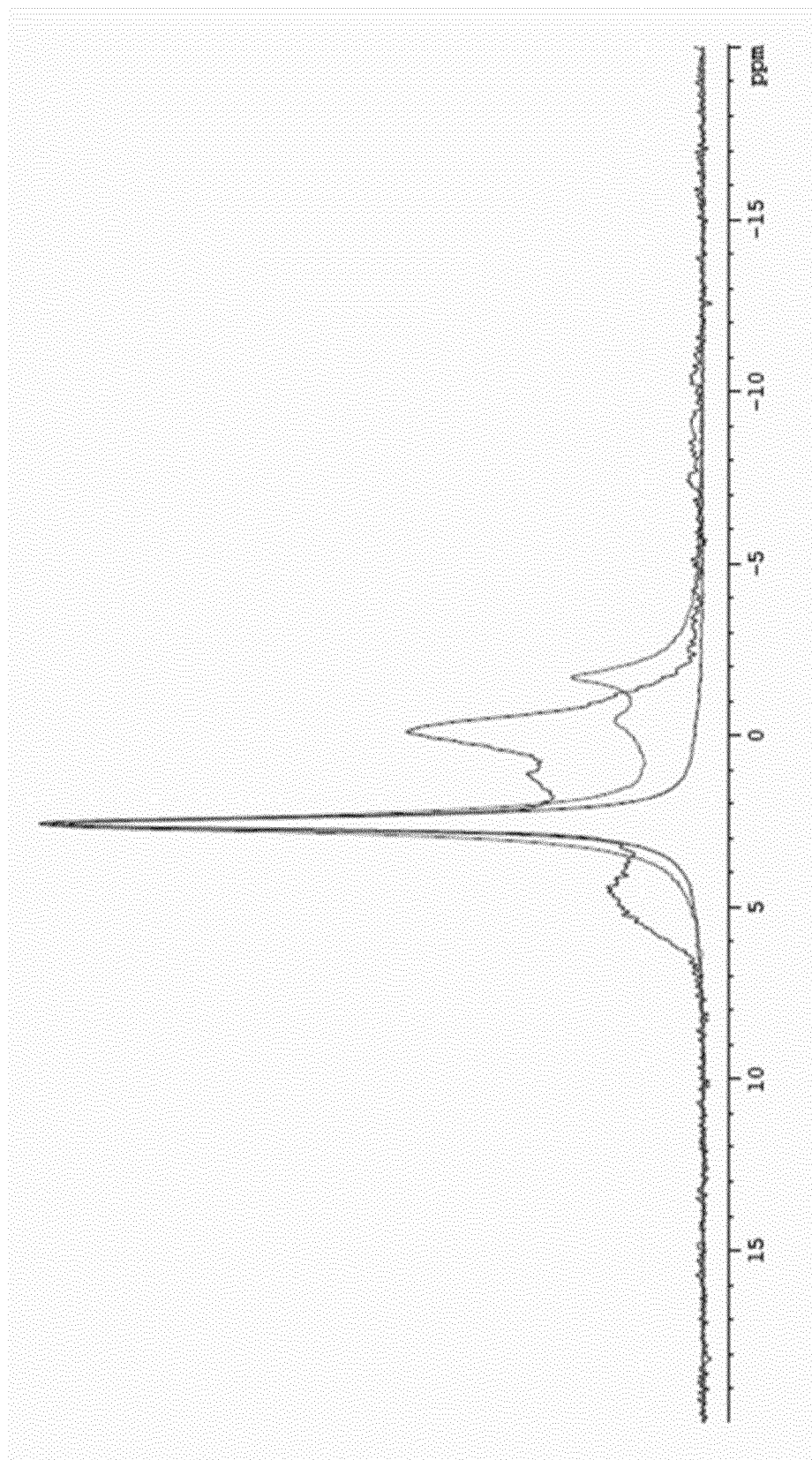
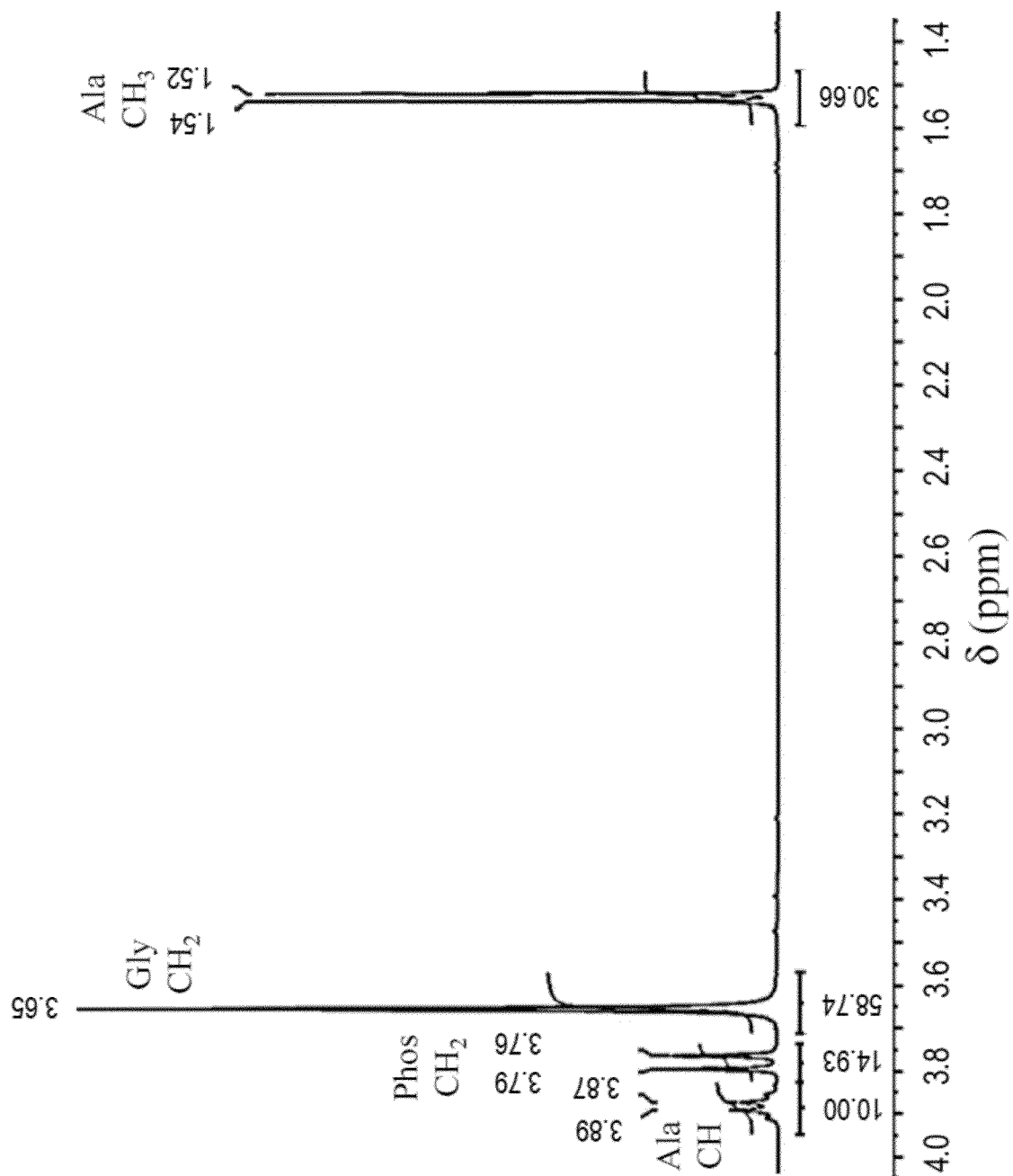
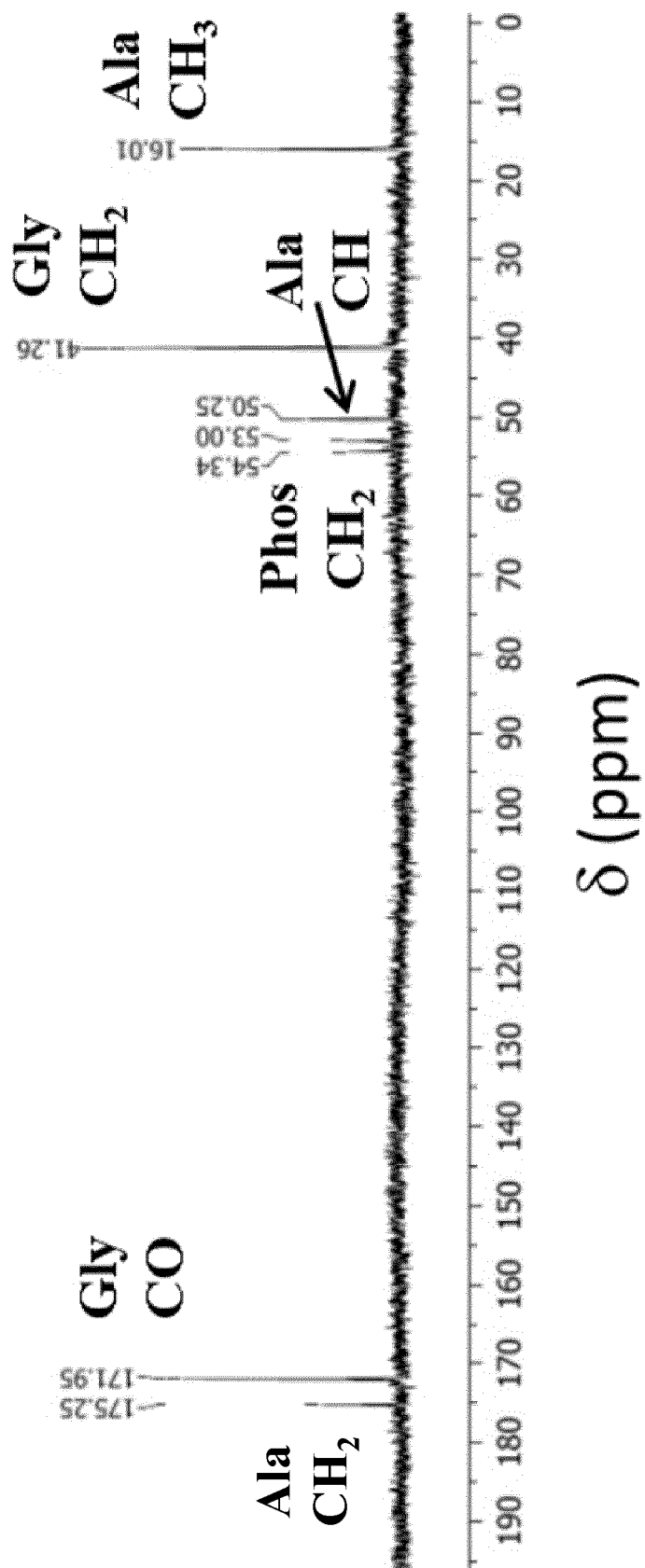


Figure 19A



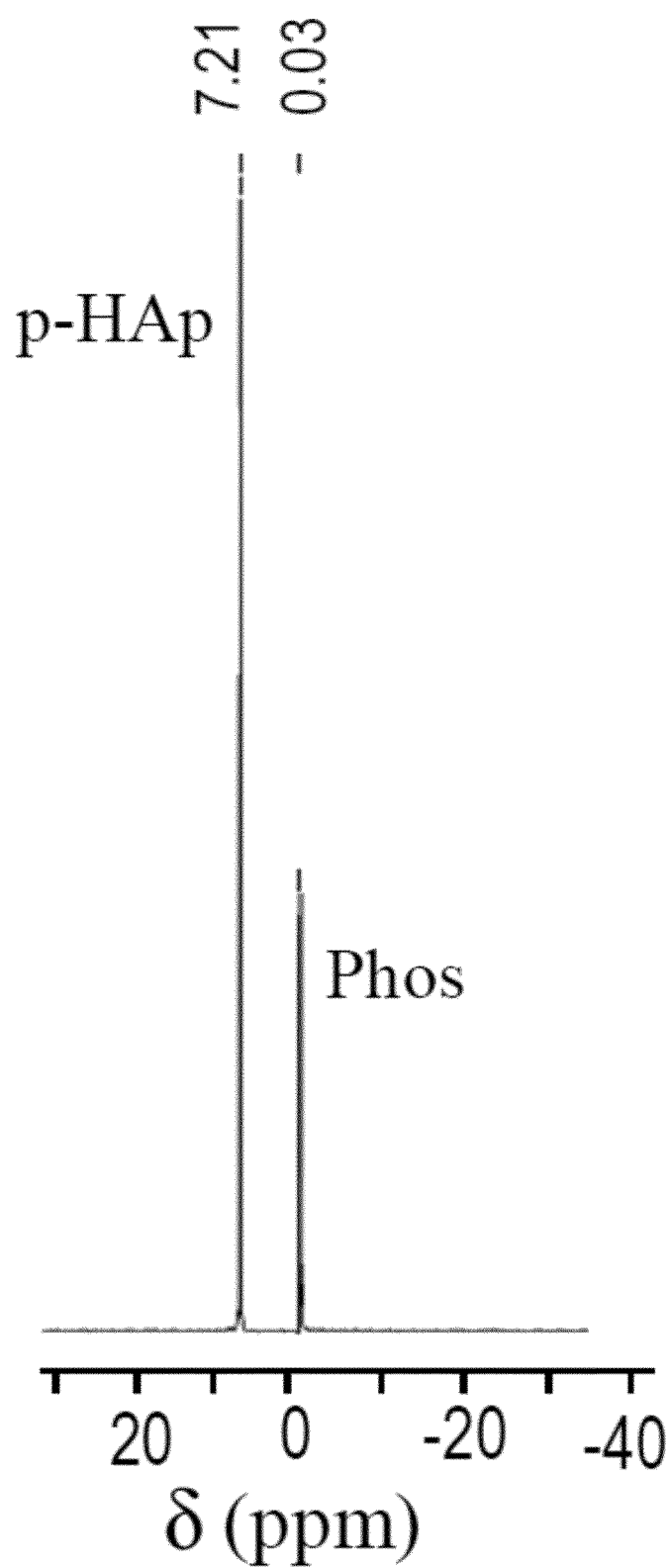
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Figure 19B



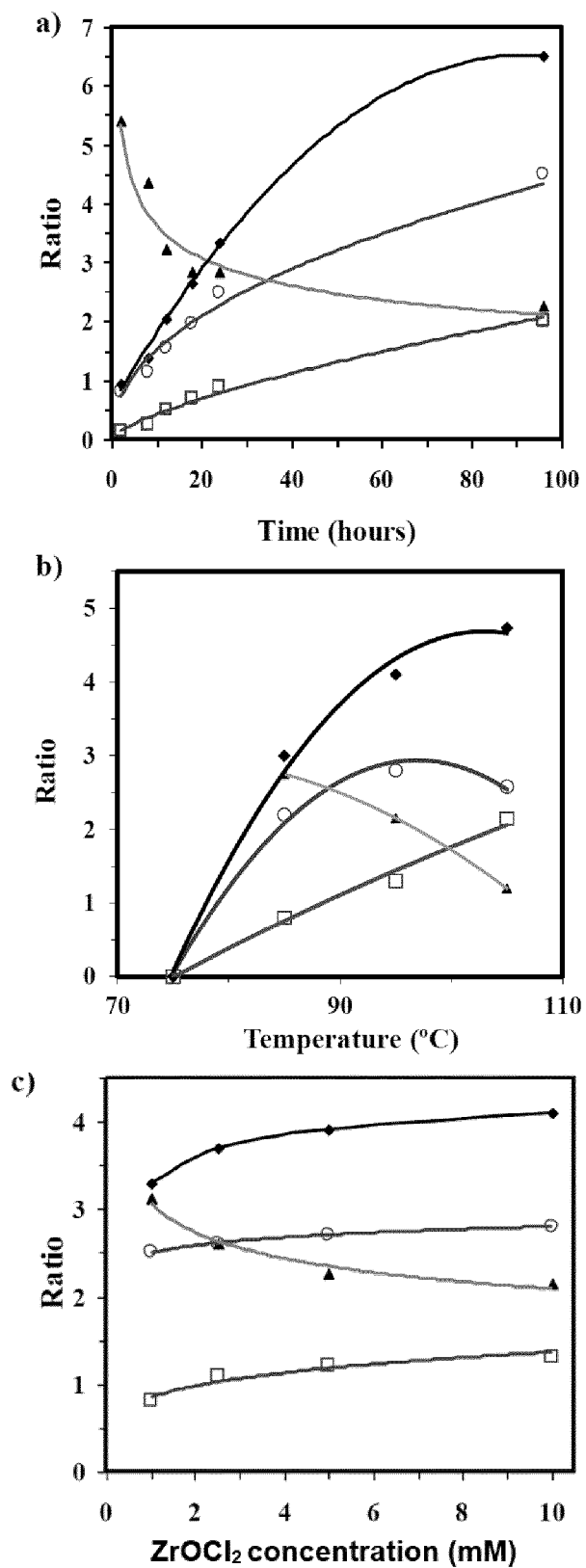
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Figure 19C



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Figure 20



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Figure 21

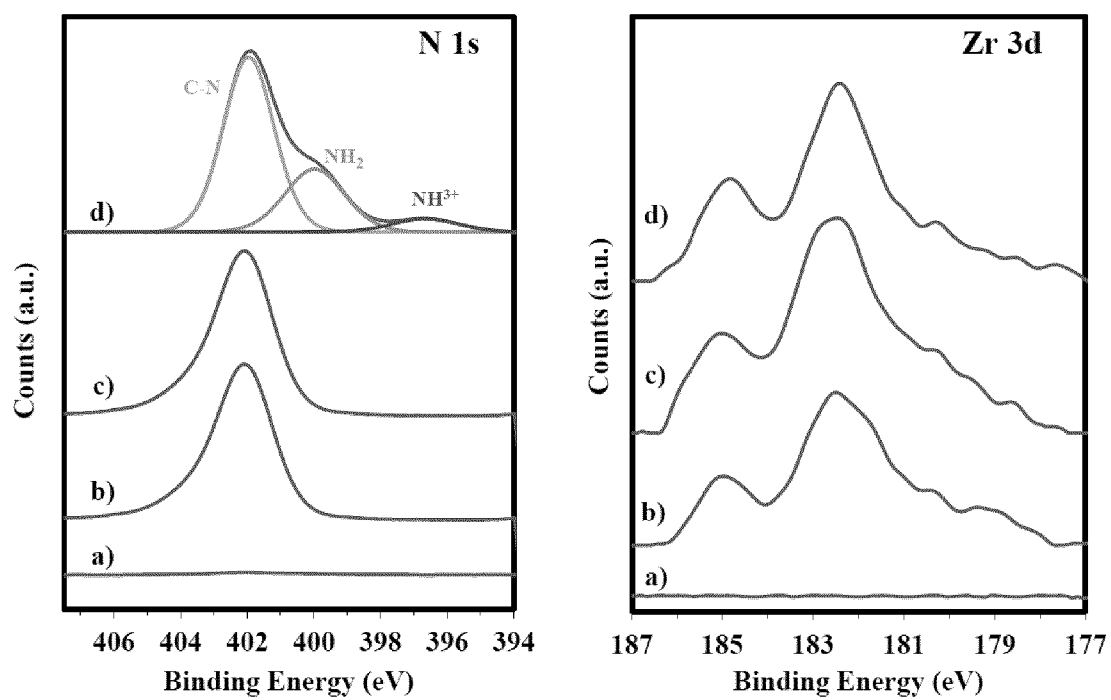


Figure 22

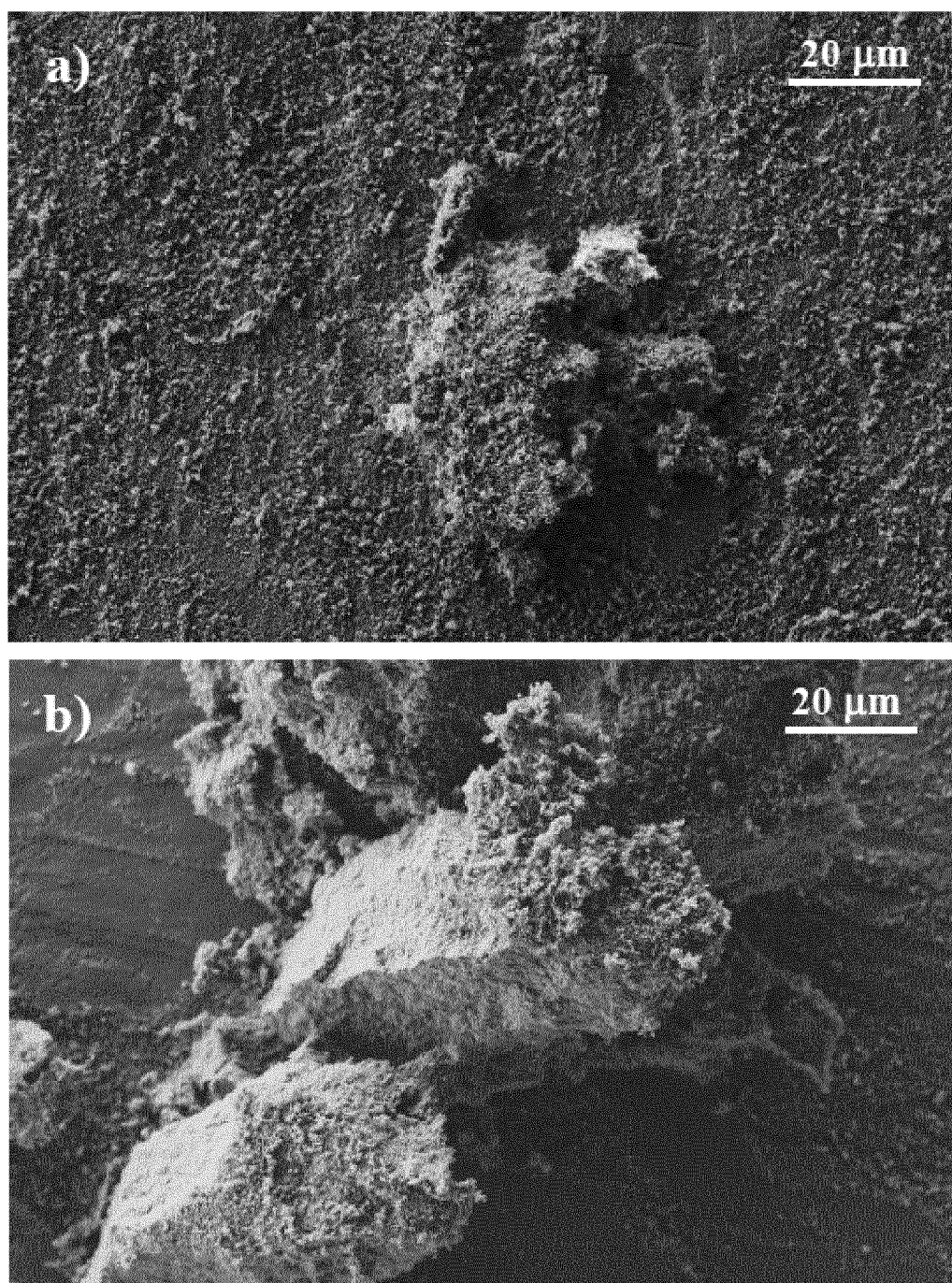


Figure 23

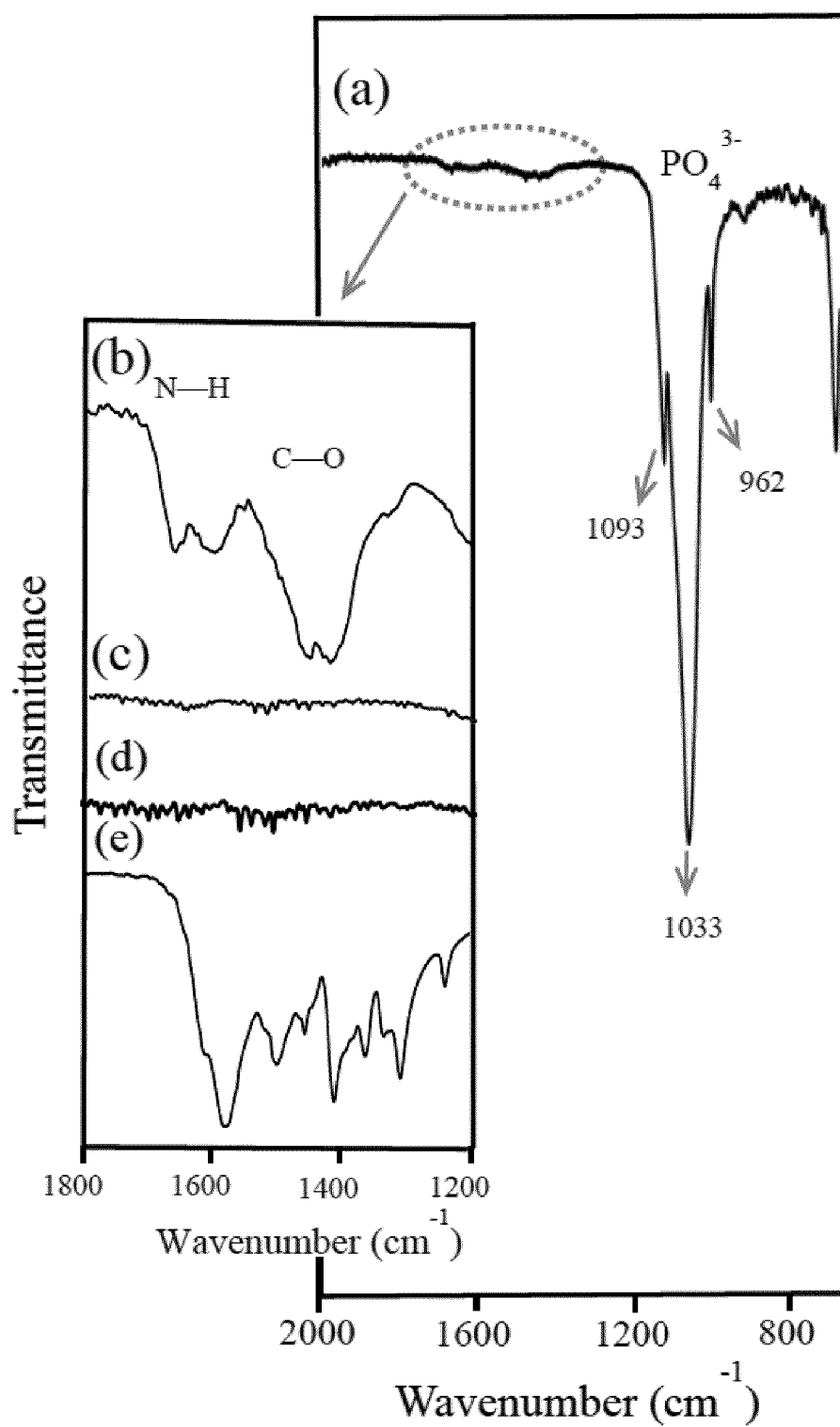
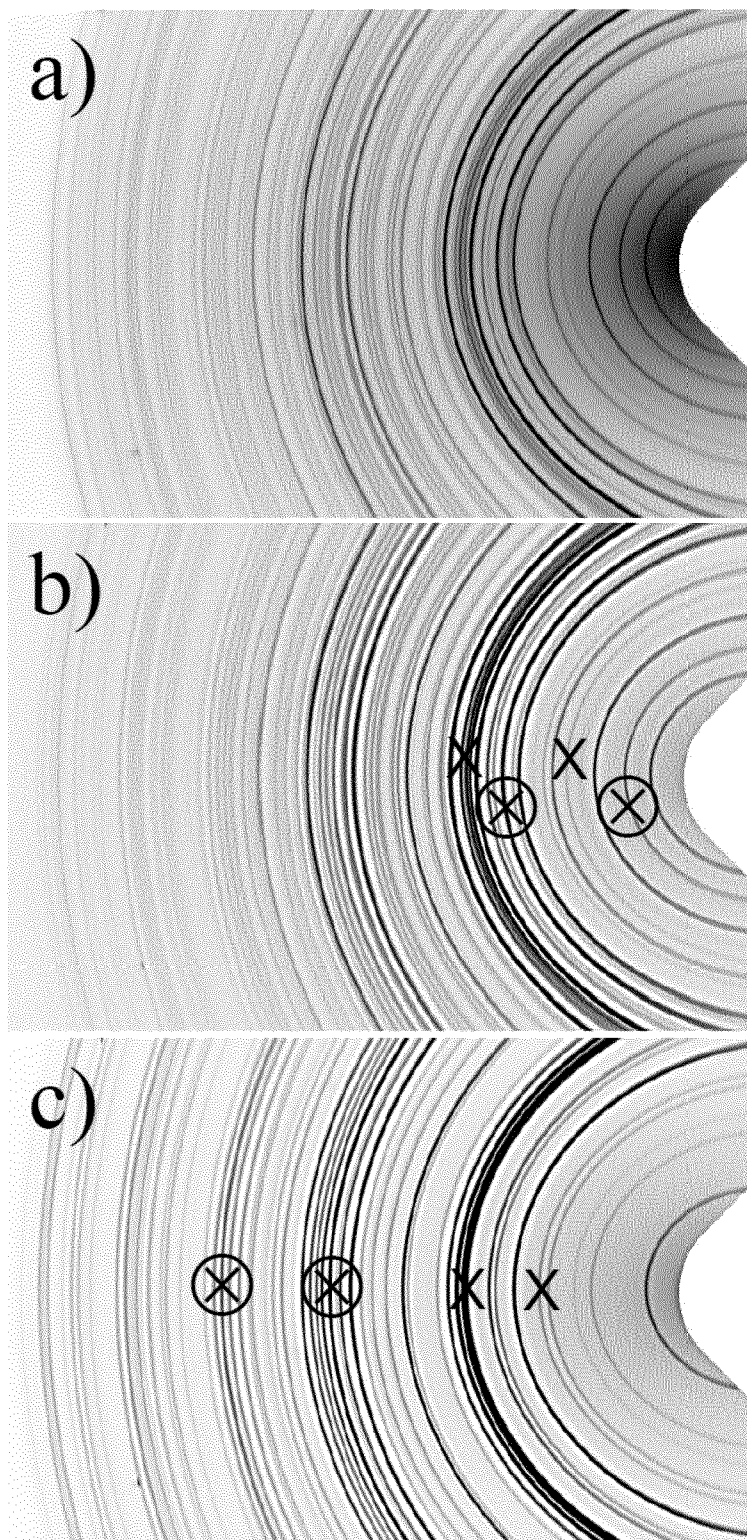


Figure 24



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Figure 25

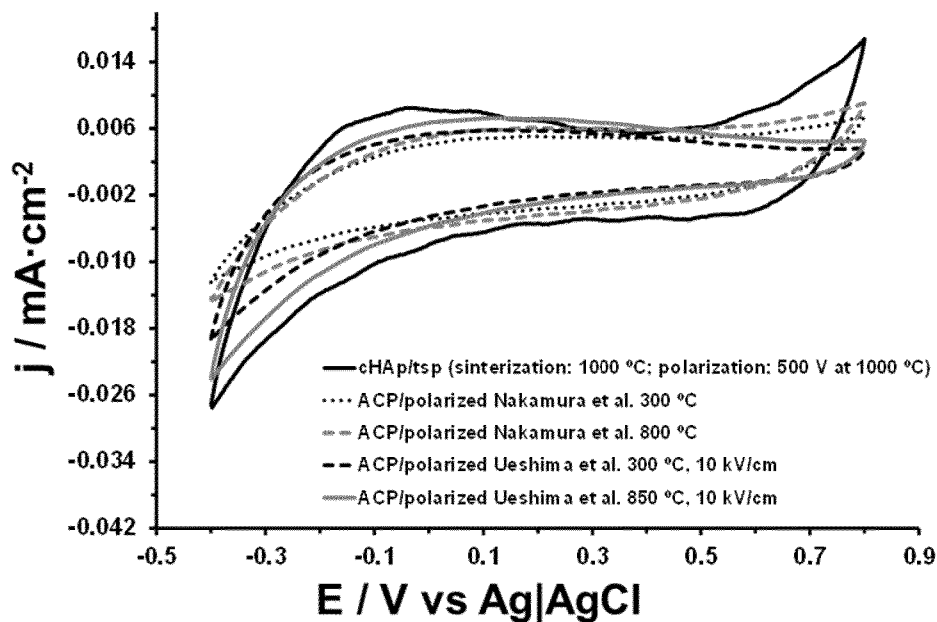
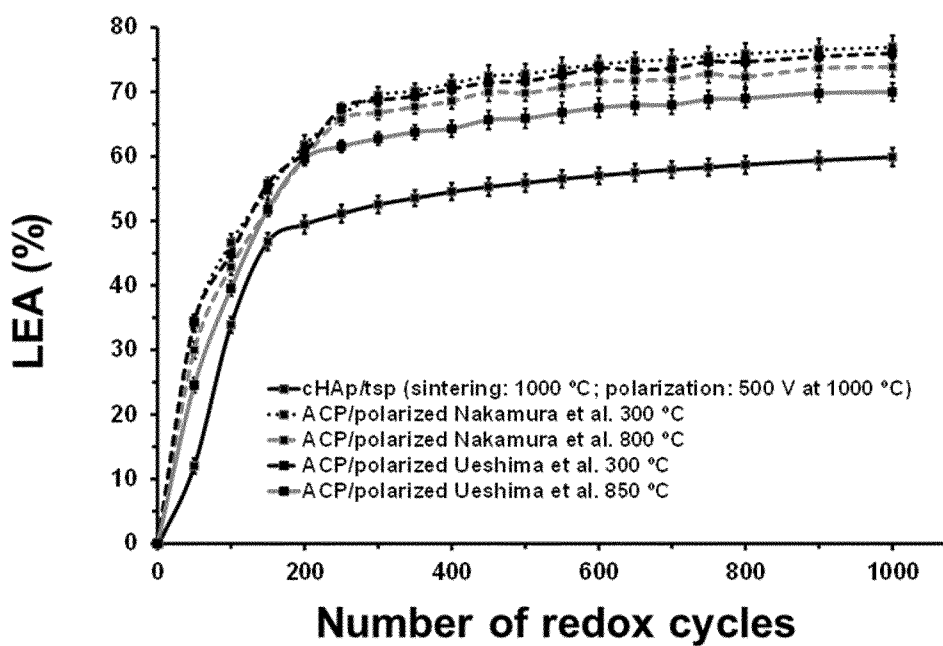


Figure 26



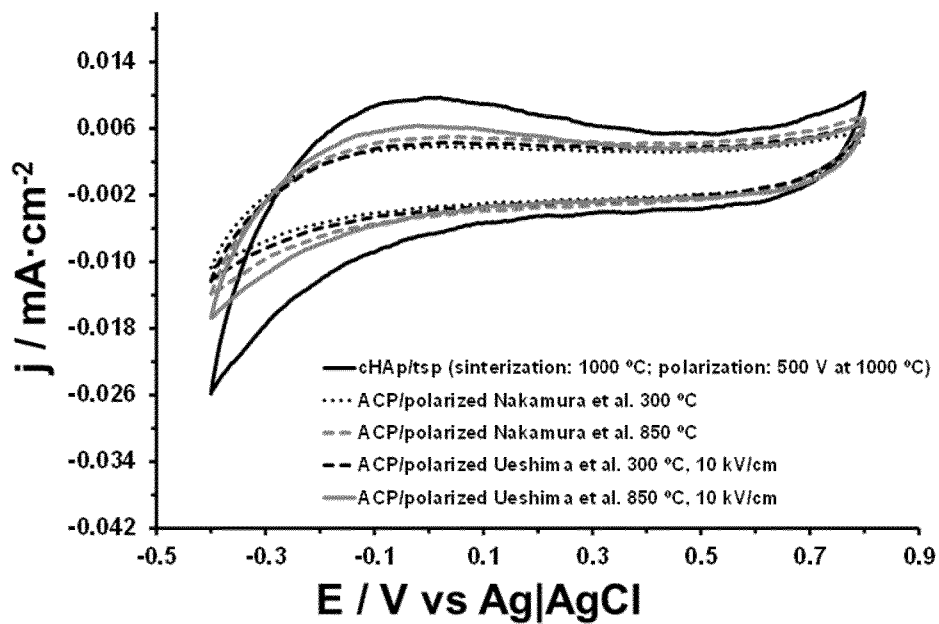
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Figure 27

SAMPLES AS PREPARED

System	Electrical resistance ($\Omega \cdot \text{cm}^2$)	Surface capacitance ($\mu\text{F/g}$)
cHAp/tsp	$0.67 \cdot 10^6$	386 ± 16
Nakamura et al. 300 °C	$0.45 \cdot 10^7$	136 ± 14
Nakamura et al. 800 °C	$0.37 \cdot 10^7$	173 ± 27
Ueshima et al. (300 °C)	$0.39 \cdot 10^7$	153 ± 15
Ueshima et al. (850°C)	$0.29 \cdot 10^7$	249 ± 9

Figure 28



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Figure 29

RE-EVALUATION OF THE SAME SAMPLES AFTER 3 MONTHS

System	Electrical resistance ($\Omega \cdot \text{cm}^2$)	Surface capacitance ($\mu\text{F/g}$)
cHAp/tsp	$0.73 \cdot 10^6$	356 ± 7
Nakamura et al. 300 °C	$0.76 \cdot 10^7$	49 ± 9
Nakamura et al. 800 °C	$0.59 \cdot 10^7$	71 ± 12
Ueshima et al. (300 °C)	$0.63 \cdot 10^7$	58 ± 9
Ueshima et al. (850°C)	$0.47 \cdot 10^7$	94 ± 12